

ITW



PATENT  
1248-0673P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Yutaka Takafuji et al. Conf.: 4125  
Appl. No.: 10/668,186 Group: 2813  
Filed: September 24, 2003 Examiner: SCHILLINGER  
For: SINGLE CRYSTAL SILICON SUBSTRATE, SOI  
SUBSTRATE, SEMICONDUCTOR DEVICE, DISPLAY  
DEVICE, AND MANUFACTURING METHOD OF  
SEMICONDUCTOR DEVICE

LARGE ENTITY TRANSMITTAL FORM

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

December 8, 2004

Sir:

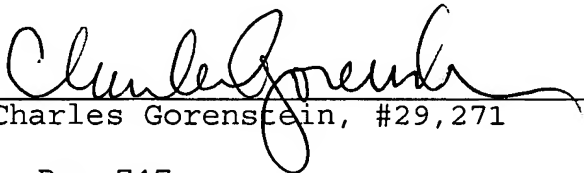
Transmitted herewith is a Reply to Restriction/Election Requirement in the above-identified application.


- ☐ The enclosed document is being transmitted via the Certificate of Mailing provisions of 37 C.F.R. § 1.8.
- ☐ Petition for \_\_\_\_\_ ( ) month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- ☒ No fee is required.
- ☐ A check in the amount of \$0.00 is enclosed.
- ☐ Please charge Deposit Account No. 02-2448 in the amount of \$0.00. A triplicate copy of this sheet is attached.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By   
Charles Gorenstein, #29,271

  
CG/CTB/mpe  
1248-0673P

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Attachment(s)



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SUBSTRATE, SEMICONDUCTOR DEVICE,  
DISPLAY DEVICE, AND MANUFACTURING  
METHOD OF SEMICONDUCTOR DEVICE

REPLY TO RESTRICTION REQUIREMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

December 8, 2004

Sir:

In reply to the Restriction Requirement dated 2004, the following remarks are respectfully submitted in connection with the above-identified application.

This reply includes: Remarks.